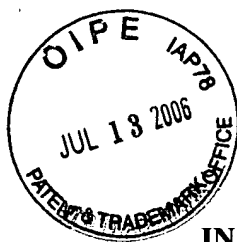


AF  
JFW



**REPLY UNDER 37 CFR §1.116**  
**EXPEDITED PROCEDURE**  
**TECHNOLOGY CENTER 1700**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:	§	
Huan-Just LIN, et al.	§	Confirmation No. 9213
	§	
Serial No.: 10/688,045	§	Group Art Unit: 1722
	§	
Filed: October 17, 2003	§	Examiner: Robert M. Kunemund
	§	
For: Fully Dry, Si Recess Free Process for	§	Docket No.: 2003-0065 / 24061.508
Removing High K Dielectric Layer	§	

**Mail Stop AF**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO FINAL OFFICE ACTION**

Sir:

No fees, including extension of time fees, are believed necessary for consideration of the present paper. However, if any fees, including extension of time fees, are necessary, the extension of time is hereby requested, and the Commissioner is hereby authorized to charge any fees, including those for the extension of time, to Haynes and Boone, LLP's Deposit Account No. 08-1394.

In response to the Final Office action of May 11, 2006, please amend the above-identified application as follows:

**Listing of claims** begins on **page 2** of this paper.

**Remarks** begin on **page 8** of this paper.